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Application Number	10/040/224
Filing Date	January 2, 2002
First Named Inventor	Ebrahim Andideh
Group Art Unit	2823
Examiner Name	Not yet assigned H. Lee
Attorney Docket Number	42390P11353

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
Lee		Pllentier, Ivan et al., "Dual Damascene Back-end Patterning Using 248nm and 193nm Lithography", Semiconductor Fabtech, 13th edition, pages 227-234	
		Hsia, Wei-Jen et al., "Flowfill Technology Low-Dielectric-Constant Materials", Semiconductor Fabtech, 10th edition, pages 291-293	
		Mills, Michael E. and McClear, Mark, "Integration Challenges of the Low-k Roadmap", http://www.future-fab.com/documents , October 18, 2001, eight pages	
		"Copper, with and without Damascene", http://www.semiconductors.net/technical/damascene_copper.htm ; October 19, 2001, four pages	
		"Damascene technology", http://www.cyberfab.net/training/selfstudy/damascene_technology_1.html ; October 19, 2001, eight pages	
		Bursky, Dave, "The Wisdom of the Ancients Meets VLSI", http://www.planetee.com/planetee/servlet ; October 19, 2001, two pages	
		"Chemical Vapor Deposition (CVD): How Performance Materials Creates High-Performance Silicon Carbide Products", http://www.performancematerial.com ; October 23, 2001, two pages	
		"PECVD", http://www.ionic.com/PECVD/pecvd.htm October 23, 2001; 2 pages	
Lee		Seaward, K.L. and Jezl, M.L., "Using Plasma Energetics to Influence Silicon Nitride Step Coverage", presented Thursday, October 5, 2000 in Session: Fundamental of Plasma Enhanced Chemical Vapor Deposition; http://www.cae.wisc.edu ; one page	

Examiner
Signature

Kuen-Ming Lee

Date

Considered

10/28/02

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¹ Applicant's unique citation designation number (optional). ² Applicant is to place a check mark here if English language Translation is attached.

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